

Very-low Dark Current in FF-CCDs

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Abstract

We achieved a dark current of 1.5 pA/cm^2 at $60 \text{ }^\circ\text{C}$ for a Full-Frame CCD with $6 \times 6 \text{ } \mu\text{m}^2$ pixel size without compromising good charge handling capacity, vertical anti-blooming, and electronic shuttering. In this paper, trade-offs in the pixel design will be discussed and results on sensor and dark current performance will be presented.¹

Introduction

In low-light level conditions, low dark current essential to capture good images. Since the largest contribution of dark current is generated by the interface states, the reduction of dark current is achieved by creating a hole layer at the entire Si-SiO₂ interface, known as multi-pinned phase (MPP) [1,2]. This approach is often used in full-frame CCDs with large pixel sizes ($12 \times 12 \text{ } \mu\text{m}^2$ or larger). Since this MPP concept does not support anti-blooming and electronic shuttering, this limits the application to specific areas of scientific imaging.

We have previously reported on our ‘all-gates-pinning’ (AGP) concept that combines MPP with both vertical anti-blooming and electronic shuttering for $6.9 \times 12.6 \text{ } \mu\text{m}^2$ [3] and $9 \times 9 \text{ } \mu\text{m}^2$ pixels [4]. We have further improved this concept in the $6 \times 6 \text{ } \mu\text{m}^2$ pixel design intended primarily for use in professional digital still photography.

Development of improved AGP pixel

In figure 1, a schematic overview of the pixel is given. AGP requires an additional n-implant below 2 of the 4 image gates compared to the standard $6 \times 6 \text{ } \mu\text{m}^2$ pixel design. In addition, the p-implant is slightly changed, so that only 2 different masks are required for introduction of AGP in our standard $6 \times 6 \text{ } \mu\text{m}^2$ sensor [5]. Extensive simulations have been done to find the optimum implant doses and conditions. Trade-offs had to be made between charge handling capacity on one hand and the pulse height required for electronic shuttering on the other hand. Two different n-implant configurations have been investigated; DN1-DN2 is 1.0-1.0 and 1.0-1.3.

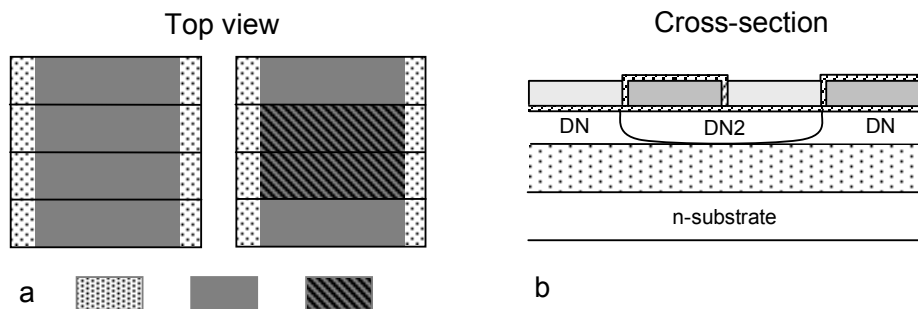


Figure 1

a) Top view of n-channel implant (DN) for conventional pixel (left) and extra n-channel implant (DN2) for AGP pixel (right). SP = channel stop implant
b) Cross section along transport direction of AGP pixel. DN is the first n-channel implant and DN2 is the second n-channel implant (non self-aligned).

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The resulting potential profiles in the pixel, under the center of the integrating and blocking gates of figure 1, is shown in figure 2.

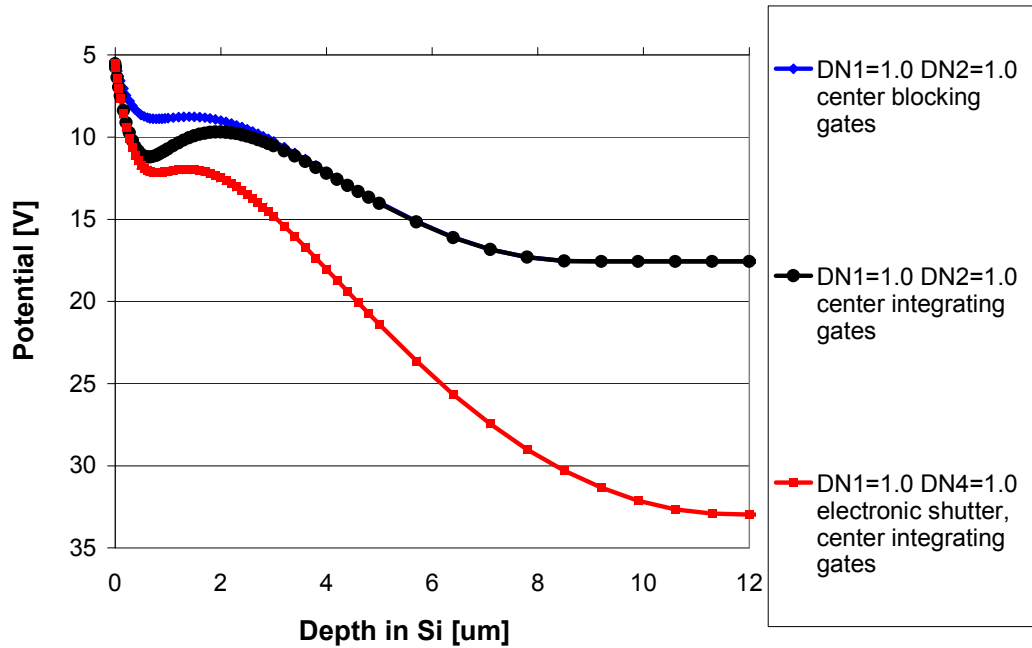


Figure 2. Potential profiles in AGP pixel

Evaluation Results

In table 1, an overview is given of the sensor performance for the two different n-implant combinations compared to the previously presented $9 \times 9 \mu\text{m}^2$ pixel results. All solutions have excellent performance on transport efficiency, quantum efficiency and vertical anti-blooming comparable to non-AGP sensors. The dark current for the $6 \times 6 \mu\text{m}^2$ pixel is improved with a factor of 2 compared to the $9 \times 9 \mu\text{m}^2$ pixel. As expected the $6 \times 6 \mu\text{m}^2$ AGP pixel with the higher charge handling capacity and thus a ‘deeper’ potential well also requires a larger pulse for electronic shuttering.

Parameter	$6 \times 6 \mu\text{m}^2$ DN1-DN2= 1.0 – 1.0	$6 \times 6 \mu\text{m}^2$ DN1-DN2= 1.0 – 1.3	$9 \times 9 \mu\text{m}^2$ [4]
Qmax (ke ⁻)	17	30	50
Vertical transport efficiency	> 0.999 995	> 0.999 995	> 0.999 995
Quantum efficiency			
@ 460 nm (%)	19	19	18
@ 530 nm (%)	29	30	24
@ 590 nm (%)	31	33	24
Electronic shutter pulse (V)	19	>20 ¹	10
Dark current at 60 °C			
(pA/cm ²)	1.5	1.7	3
(e ⁻ /s/pixel)	3.4	3.8	16

¹ 20V is current hardware limit

Table 1 Overview of performance of different AGP variants.

In figure 3, a comparison of dark current histograms with and without AGP for the $6 \times 6 \mu\text{m}^2$ pixel is given. Figure 4 shows the corresponding images in dark. The suppression of dark current by creating the hole layer at the interface equals a factor 80 at 60°C . In figure 5, the dark current as a function of the temperature is plotted. The temperature dependence is different for the different AGP pixels. More investigation is ongoing to explain this spread in temperature dependence. In figure 6, an Arrhenius plot of the pixel dark current for 1.0-1.0 implant configuration is depicted. This curve shows two different temperature regions. For temperatures above 300 K the thermal generation model with an activation energy of 0.72 eV describes the dark current. For temperatures below 273 K the dark current stabilizes at 0.06 pA/cm^2 . For temperatures below 225 K no data is available. Electronic shuttering is functioning properly over the whole temperature region. More research is required to explain this stabilization at 0.06 pA/cm^2 , but Takayanagi *et al.* [6] reported a similar behavior.

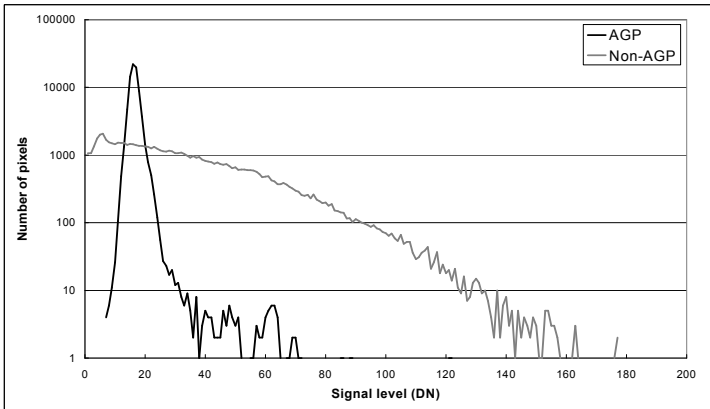


Figure 3 Histogram of dark current at room temperature for $6 \times 6 \mu\text{m}^2$ pixel with and without AGP with an integration time of 6 s .

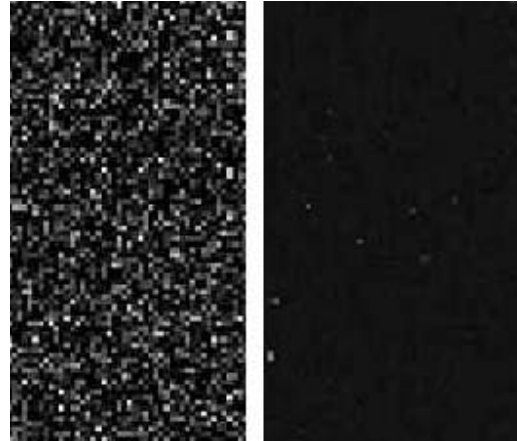


Figure 4. Dark images obtained under similar conditions without and with AGP (partial image only is shown)

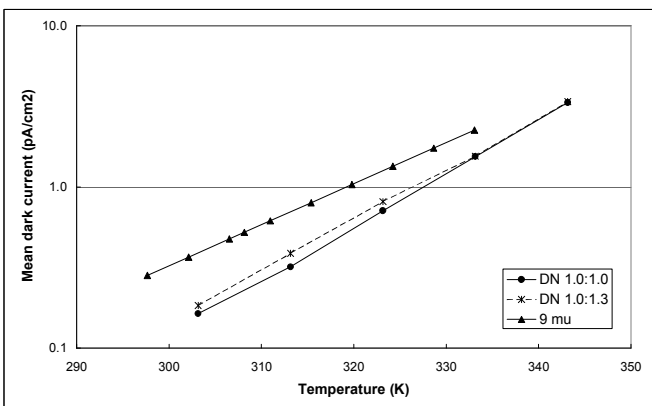


Figure 5 Dark current of various AGP pixels versus temperature

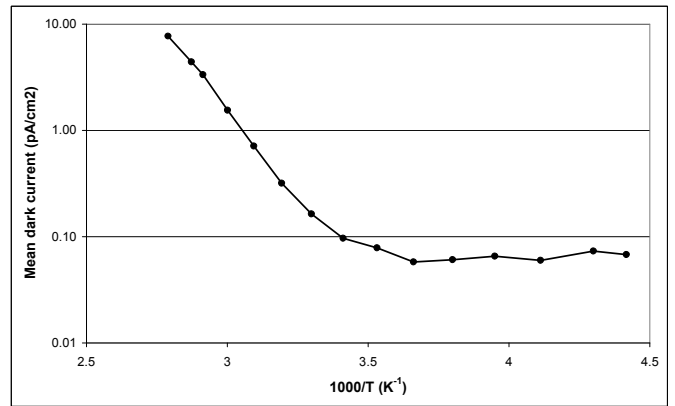


Figure 6 Dark current of $\text{DN1-DN2}=1.0-1.0$ configuration versus reciprocal temperature

Due to the very-low dark current levels, peaks of deep level traps are now clearly detectable as shown in figure 7. In figure 8, the Arrhenius plot of these 5 different peaks is shown and in table 2 the corresponding activation energies are given. An in-depth analysis of the origin of these deep level traps still needs to be performed.

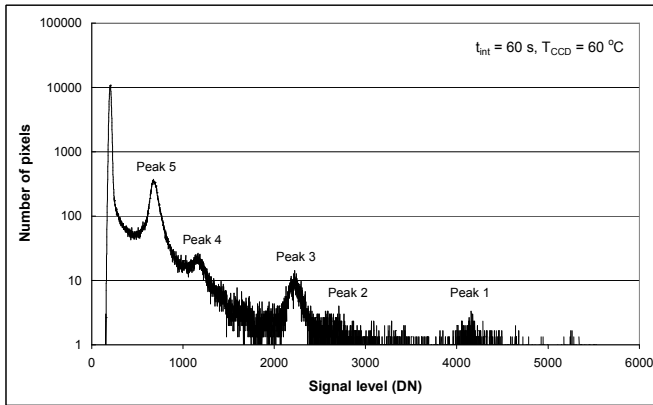


Figure 7 Histogram of dark current of DN1-DN2=1.0-1.0 configuration at 60 °C with 60 s integration time.

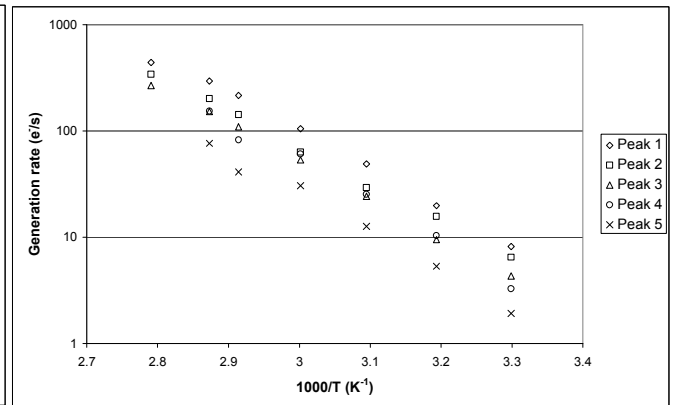


Figure 8 Generation rate of deep level traps versus reciprocal temperature observed in dark current histograms

Peak	Activation energy (eV)	Generation rate @ 60 °C (e-/s)
1	0.74	104.8
2	0.68	63.2
3	0.73	53.3
4	0.89	25.3
5	0.85	12.6

Table 2 Properties of deep level traps observed in dark current histogram.

Summary & Conclusions

We further improved the AGP concept for 6x6 μm^2 pixel resulting in, to the best of our knowledge, a new world-record dark current of 1.5 pA/cm² (3.4 e-/pixel/s) at 60 °C. Other CCD parameters were not affected. This CCD AGP image sensor concept is well suited for applications requiring low noise levels without cooling, like professional digital photography, medical and scientific imaging.

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References

1. J. Hynccek, "Virtual Phase Technology", *IEDM Technical Digest*, pp. 611-614, 1979
2. B.E. Burke and S.A. Gajar, "Dynamic Suppression of Interface-State Dark Current in Buried-Channel CCD's", *IEEE Trans. Electron Devices*, vol. 38, pp. 285-290, Feb. 1991
3. J. Bosiers, *et al.*, "A S-VHS compatible 1/3" 720(H) * 588(V) FT-CCD with low dark current by surface pinning", *Proc. IEDM'93* pp.97-100
4. I. Peters *et al.*, "Dark current reduction in FF-CCDs", *2005 CCD & AIS Workshop*, Karuizawa, Japan
5. E.-J. Manoury *et al.*, "A 36x48mm² 48M-pixel CCD imager for professional DSC applications", *Tech. Digest IEDM*, 2008.
6. Takayanagi *et al.*, "Dark current reduction in stacked-type CMOS-APS for charged particle imaging", *IEEE Trans. Electron Devices*, vol. 50, pp. 70-76, 2003.